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PATENT 81839.0102

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Art Unit: Not assigned

Michihiro MIZUNO

Examiner: Not assigned

Serial No: Not assigned

Filed: September 25, 2001

For: METHOD FOR EVALUATING CONCENTRATION

OF METAL IMPURITIES IN SILICON WAFER

TRANSMITTAL OF INFORMATION DISCLOSURE STATEMENT

Box PCT Assistant Commissioner for Patents Washington, D.C. 20231

Dear Sir:

The information disclosure statement submitted herewith is being filed concurrently with the subject application [37 C.F.R. § 1.97(b)] and contains items of information cited in the parent application No. PCT/JP01/00301.

If it should be determined that for any reason either an insufficient or excessive fee has been paid, please charge any insufficiency or credit any overpayment necessary to ensure consideration of the information disclosure statement for the above-identified application to Deposit Account No. 50-1314. A copy of this paper is enclosed.

Respectfully submitted,

HOGAN & HARTSON L.L.P.

Date: September 25, 2001

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Docket Number (Option) **FORM PTO-1449** Not assigned 81839.010 **Applicant** INFORMATION DISCLOSURE CITATION Michihiro MIZUNO IN AN APPLICATION **Group Art Unit** Filing Date (Use several sheets if necessary) Not assigned September 25, 2001 U.S. PATENT DOCUMENTS **FILING DATE IF SUBCLASS EXAMINER CLASS** NAME DATE **APPROPRIATE DOCUMENT NUMBER** INITIAL FOREIGN PATENT DOCUMENTS **TRANSLATION SUBCLASS CLASS** COUNTRY DATE (YES/NO) DOCUMENT NUMBER 11/7/90 Japan 02-272359 1/7/00 Japan 2000-002632 OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) DATE CONSIDERED **EXAMINER** EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.